FORM PTO-1449

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Applicant:

Serial No.: 09/960,659

LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT

Pradeep K. Agarwal et al

Filing Date Group Art:

September 21, 2001 1724

U.S. PATENT DOCUMENTS

iner al	Document No.	Date	Name	Class	Sub Class	Filing Date
AA	4,358,297	11/09/82		Class		If Appropriate
AB	5,211,923	05/18/93			-/-	
AC	5,520,894	05/28/96		1/		
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AF				FA	50	42
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FOREIGN PATENT DOCUMENTS

6	AM AN	Document No. 675,282	Date 12/03/63	Country Canada	Class	Sub Class	Translation Yes No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

- Q	AO	Harkness et al, Hydrogen Sulfide Waste Treatment by M.
	AP	Harkness et al, Hydrogen Sulfide Waste Treatment by Microwave Plasma Dissociation, pgs. 197 – 202, 1990 Helfritch, Pulsed Corona Discharge for Hydrogen S. 10.1. D.
J	AQ	Helfritch, Pulsed Corona Discharge for Hydrogen Sulfide Decomposition, pgs. 882 –886, 1993. Bagautdinov et al, Plasma Chemical Production of Units.
<u> </u>		Bagautdinov et al, Plasma Chemical Production of Hydrogen from H ₂ S-Containing Gases in MCW Discharge, pgs. 193 –
EXAMI		W. MAYRUAN DATE CONSIDERED 3/11/

DATE CONSIDERED:

3/15/03

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.